

U.S. Department of Commerce, Patent and Trademark Office					Docket No.	Serial No.
(PTO Form 149 modified)					7938/ETCH/SILICON 10/628,001	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>OCT 30 2003</i>					Applicant Davis, et al.	Confirmation No.:
(Use several sheets if necessary)					Filing Date 07/25/03	Group
Examiner						

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
<i>AS</i>	A1	6,419,846	07/16/2002	Toprac et al.	216	60	<i>CS</i>
<i>AS</i>	A2	6,521,080	02/18/2003	Balasubramhanya et al.	156	345.24	<i>CS</i>
	A3						<i>CS</i>
	A4						<i>CS</i>
	A5						<i>CS</i>
	A6						<i>CS</i>
	A7						<i>CS</i>
	A8						<i>CS</i>
	A9						<i>CS</i>
	A10						<i>CS</i>

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>
	B4						<input type="checkbox"/>	<input type="checkbox"/>
	B5						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
<i>AS</i>	C1	Yue, et al., "Plasma etching endpoint detection using multiple wavelengths for small open-area wafers," J. Vac. Sci. Technol. A, 19(1), Jan/Feb 2001, 66-75
	C2	
	C3	

Examiner *AS* Date Considered *07-08-03*

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.